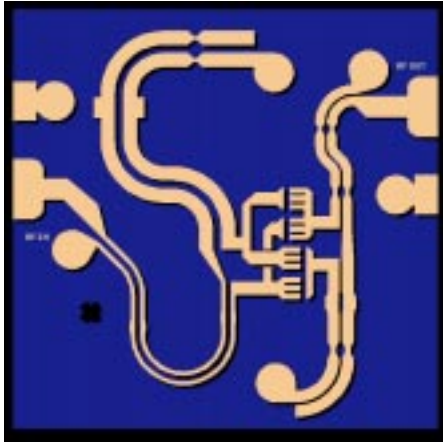


**20 - 40 GHz X2 Frequency Multiplier**

**TGC1430F-EPU**



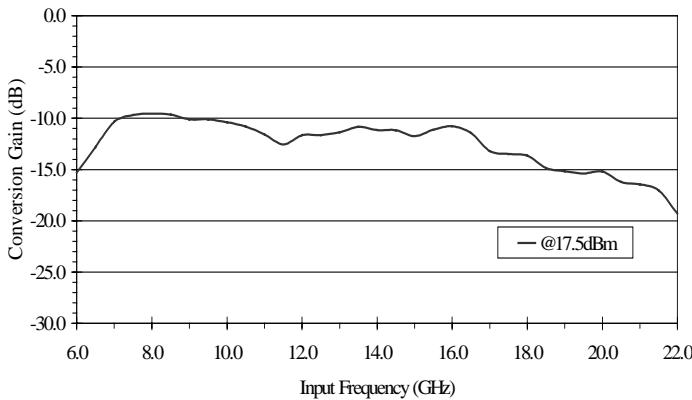
Chip Dimensions 1.50 mm x 1.50 mm

**Key Features and Performance**

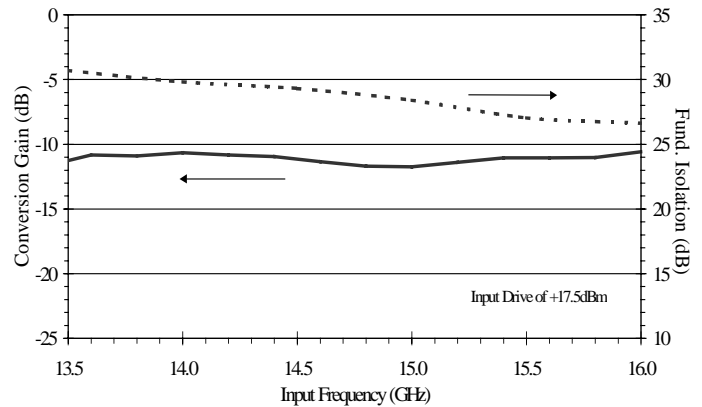
- 0.25um pHEMT Technology
- 20 - 40 GHz Output Frequencies
- 10 - 20 GHz Fundamental Frequencies
- -12 +/- 2dB Conversion Gain
- 18 dBm Input Drive Optimum
- 25dB Fundamental Isolation

**Primary Applications**

- Point-to-Point Radio
- Point-to-Multipoint Communications



**Conversion Gain vs Input Frequency (Input @ 17.5dBm)**



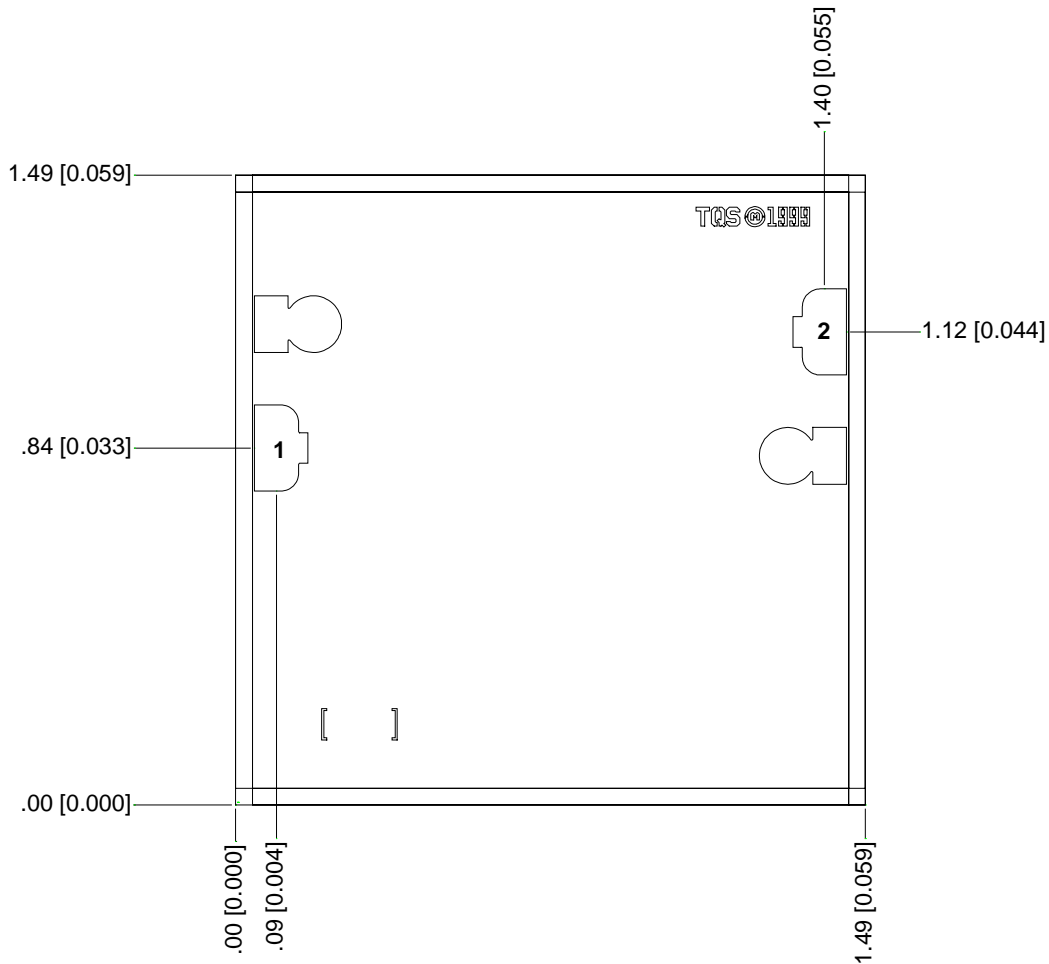
**Conversion Gain and Fundamental Isolation for 27 - 32 GHz Output**



**Fundamental Isolation**

Note: Devices designated as EPU are typically early in their characterization process prior to finalizing all electrical and process specifications. Specifications subject to change without notice

**Mechanical Drawing**



**Units: millimeters [inches]**

**Thickness: 0.10 [0.004] (reference only)**

**Chip edge to bond pad dimensions are shown to center of bond pads.**

**Chip size tolerance: ±0.05 [0.002]**

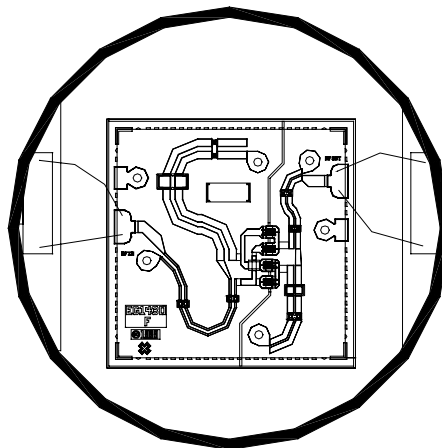
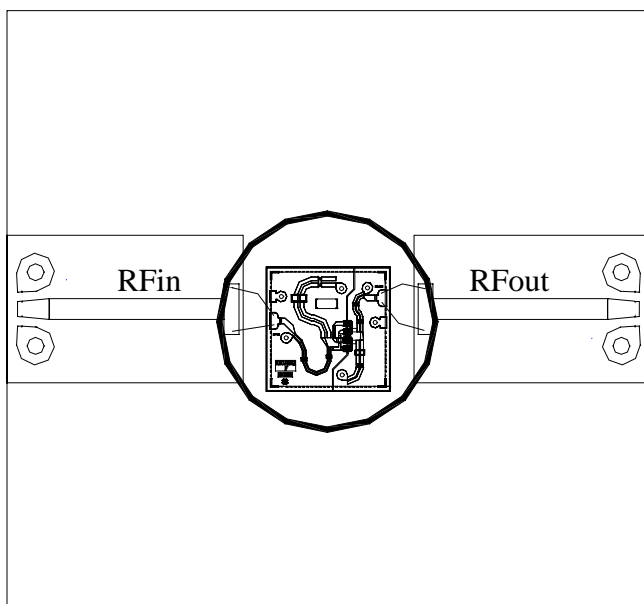
**RF ground through backside**

<b>Bond Pad #1</b>	<b>RF Input</b>	<b>0.10 x 0.20</b>	<b>[0.004 x 0.008]</b>
<b>Bond Pad #2</b>	<b>RF Output</b>	<b>0.10 x 0.20</b>	<b>[0.004 x 0.008]</b>

***GaAs MMIC devices are susceptible to damage from Electrostatic Discharge. Proper precautions should be observed during handling, assembly and test.***

*Note: Devices designated as EPU are typically early in their characterization process prior to finalizing all electrical and process specifications. Specifications subject to change without notice*

### Recommended Assembly Drawing



Attach 2 TFNs and MMIC to carrier plate as shown using conductive epoxy.  
Bond 4 wires as shown using minimum length.

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*Note: Devices designated as EPU are typically early in their characterization process prior to finalizing all electrical and process specifications. Specifications subject to change without notice*

## **Assembly Process Notes**

### Reflow process assembly notes:

- Use AuSn (80/20) solder with limited exposure to temperatures at or above 300°C (30 seconds max).
- An alloy station or conveyor furnace with reducing atmosphere should be used.
- No fluxes should be utilized.
- Coefficient of thermal expansion matching is critical for long-term reliability.
- Devices must be stored in a dry nitrogen atmosphere.

### Component placement and adhesive attachment assembly notes:

- Vacuum pencils and/or vacuum collets are the preferred method of pick up.
- Air bridges must be avoided during placement.
- The force impact is critical during auto placement.
- Organic attachment can be used in low-power applications.
- Curing should be done in a convection oven; proper exhaust is a safety concern.
- Microwave or radiant curing should not be used because of differential heating.
- Coefficient of thermal expansion matching is critical.

### Interconnect process assembly notes:

- Thermosonic ball bonding is the preferred interconnect technique.
- Force, time, and ultrasonics are critical parameters.
- Aluminum wire should not be used.
- Maximum stage temperature is 200°C.

***GaAs MMIC devices are susceptible to damage from Electrostatic Discharge. Proper precautions should be observed during handling, assembly and test.***

*Note: Devices designated as EPU are typically early in their characterization process prior to finalizing all electrical and process specifications. Specifications are subject to change without notice.*